

**IN THE CLAIMS**

1. (Currently Amended) A method for fabricating an organic thin film comprising the steps of:

forming an undercoating film made of silicon nitride or silicon nitride oxide on a substrate;

wet-cleaning said undercoating film using a cleaning liquid;

irradiating far ultraviolet ray onto said undercoating film of which wet-cleaning has been completed; and

forming an organic thin film on said undercoating film onto which far ultraviolet ray has been irradiated by turning said substrate and supplying a liquid organic material onto said substrate,

wherein said cleaning liquid is a CO<sub>2</sub>-dissolved water.

2. (Original) The method for fabricating an organic thin film according to claim 1, wherein said step of wet-cleaning includes the step of applying ultrasonic wave in said cleaning liquid.

3. (Original) The method for fabricating an organic thin film according to claim 1, further comprising a step of forming another organic thin film on said undercoating film and then removing this organic thin film between the step of depositing said undercoating film and the step of wet-cleaning.

4. (Original) The method for fabricating an organic thin film according to claim 1, wherein said step of irradiating far ultraviolet ray includes a step of performing heat treatment on said substrate.

5. (Original) The method for fabricating an organic thin film according to claim 1, wherein a total amount of said liquid organic material used in the step of forming said organic thin film is at least 0.8ml.

6. (Currently Amended) A method for fabricating an organic thin film comprising the steps of:

forming an undercoating film made of silicon nitride or silicon nitride oxide on a substrate;

wet-cleaning said undercoating film using a cleaning liquid; and

forming an organic thin film on said undercoating film of which wet-cleaning has been completed by turning said substrate and supplying a liquid organic material onto said substrate;

wherein said organic material contains at least one solvent selected from the group consisting of propylene glycol monomethyl ether acetate, propylene glycol monomethyl ether, ethyl lactate, methyl methoxy propionate, ethyl ethoxy propionate, 2-heptanone, ethyl pyruvate, diethylene glycol monomethyl ether, methyl cellosolve acetate, propylene glycol monoethyl ether acetate, ethyl methoxy propionate, methyl lactate and methyl pyruvate,

wherein said cleaning liquid is a CO<sub>2</sub>-dissolved water.

7. (Original) The method for fabricating an organic thin film according to claim 6, wherein said step of wet-cleaning includes the step of applying ultrasonic wave in said cleaning liquid.

8. (Original) The method for fabricating an organic thin film according to claim 6, further comprising the step of forming another organic thin film on said undercoating film and then removing this organic thin film between the step of forming said undercoating film and the step of wet-cleaning.

9. (Original) The method for fabricating an organic thin film according to claim 6, wherein a total amount of said liquid organic material used in the step of forming said organic thin film is at least 0.8ml.

10. (Currently Amended) A method for fabricating an organic thin film comprising the steps of:

forming an undercoating film made of silicon nitride or silicon nitride oxide on a substrate;

irradiating far ultraviolet ray onto said undercoating film while heating said substrate; and

forming an ~~organic thin~~ anti-reflection film made of a liquid organic material on said undercoating film onto which far ultraviolet ray has been irradiated, by turning said substrate and supplying a liquid organic material onto said substrate;

~~wherein said organic material contains at least one solvent selected from the group consisting of propylene glycol monomethyl ether acetate, propylene glycol monomethyl ether,~~

~~ethyl lactate, methyl methoxy propionate, ethyl ethoxy propionate, 2-heptanone, ethyl pyruvate, diethylene glycol monomethyl ether, methyl cellosolve acetate, propylene glycol monoethyl ether acetate, ethyl methoxy propionate, methyl lactate and methyl pyruvate.~~

11. (Cancelled)

12. (Original) The method for fabricating an organic thin film according to claim 10, wherein a total amount of said liquid organic material used in the step of forming said organic thin film is at least 0.8ml.

13. (Cancelled)

14. (Previously Presented) The method for fabricating an organic thin film according to claim 1, wherein said organic material is an organic material of low viscosity.

15. (Cancelled)

16. (Previously Presented) The method for fabricating an organic thin film according to claim 6, wherein said organic material is an organic material of low viscosity.

17. (Previously Presented) The method for fabricating an organic thin film according to claim 10, wherein said organic material is an organic material of low viscosity.

18. (New) The method for fabricating an organic thin film according to claim 10, wherein said organic material contains at least one solvent selected from the group consisting of propylene glycol monomethyl ether acetate, propylene glycol monomethyl ether, ethyl lactate, methyl methoxy propionate, ethyl ethoxy propionate, 2-heptanone, ethyl pyruvate, diethylene glycol monomethyl ether, methyl cellosolve acetate, propylene glycol monoethyl ether acetate, ethyl methoxy propionate, methyl lactate and methyl pyruvate

19. (New) The method for fabricating an organic thin film according to claim 10, wherein said anti-reflection film has a thickness of about 100nm or thinner.